

Construction and Working of Enhancement-Type MOSFET

MOSFET \rightarrow Active device

Any type of device has ability to control the flow of electron is known as Active device

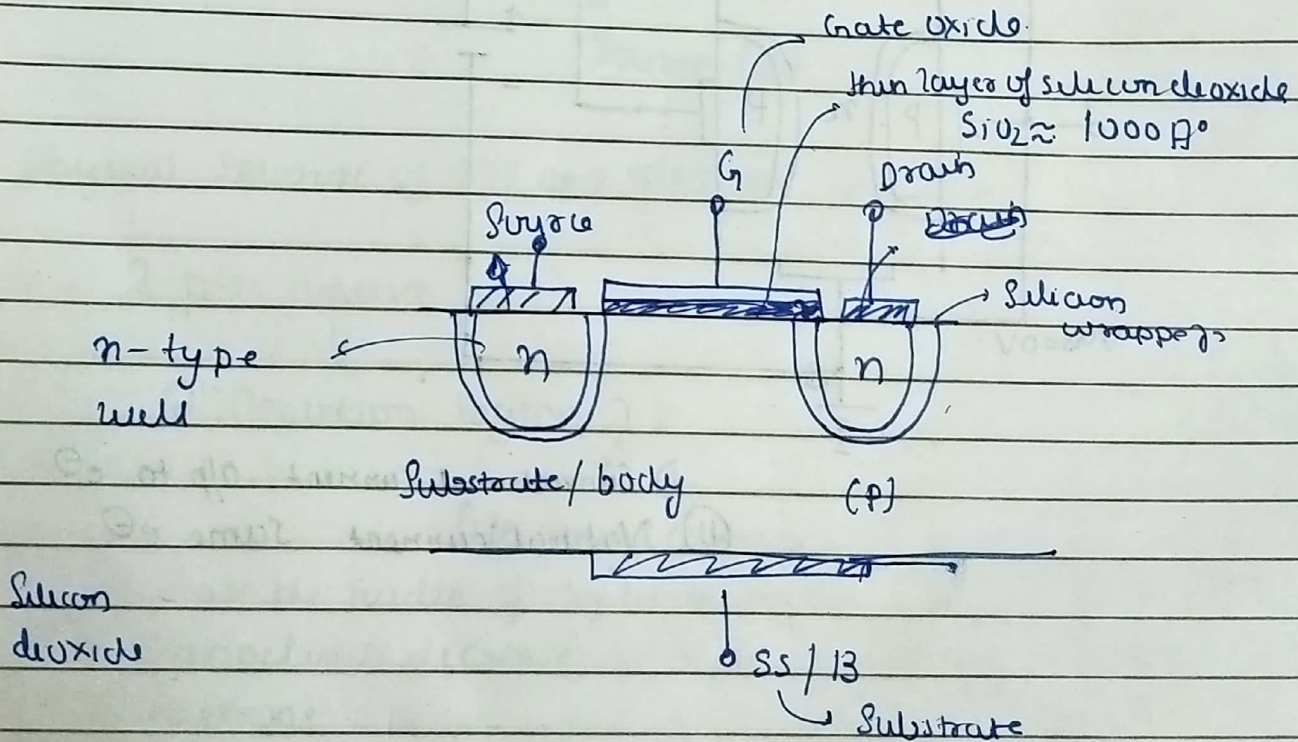
ex \rightarrow BJT, JFET

Passive device

ex \rightarrow Diode, Capacitors, Transformer etc

1) Depletion type MOSFET \rightarrow $\begin{cases} \text{n-channel} \\ \text{p-channel} \end{cases}$
Ch \checkmark D and S

2) Enhancement Type MOSFET \rightarrow $\begin{cases} \text{n-channel} \\ \text{p-channel} \end{cases}$
Ch X D and S



The majority charge carriers \rightarrow holes

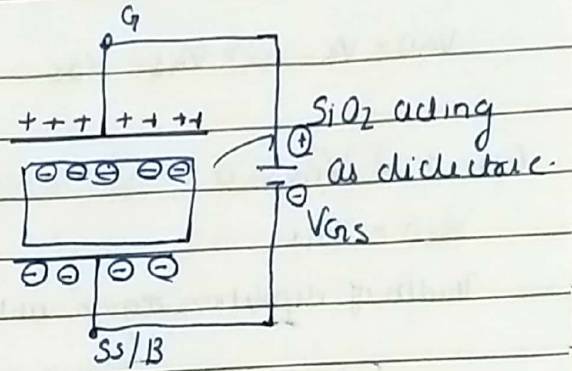
minority charge carriers $\rightarrow e^-$

mobile C.C = Immobile ions

We have Gate more positive

Inversion:

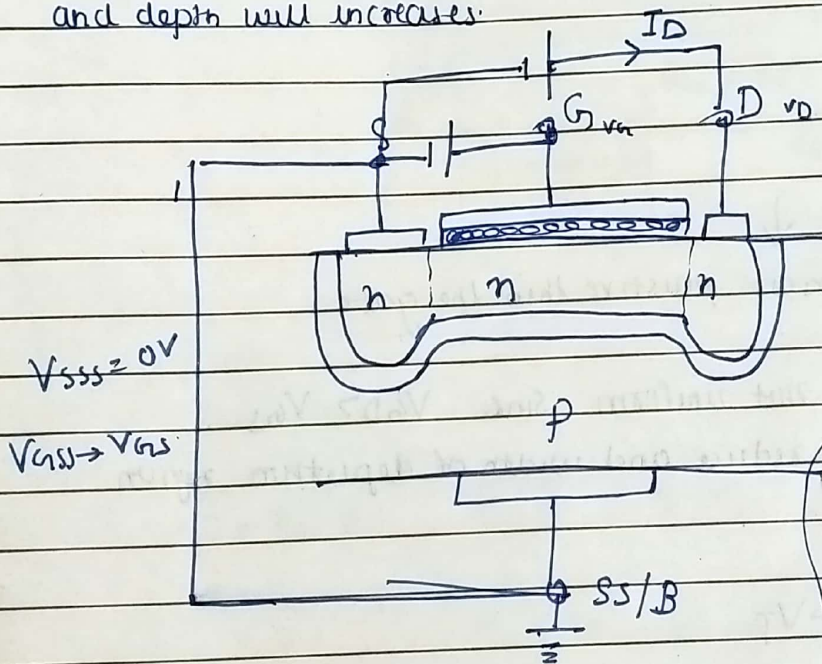
We change n-type to p-type
by making gate terminal
positive



So channel is formed.

$V_{GS} > 0$, Inversion will
happen p-type to n-type
So conductive channel
is formed between
source and drain
ch. width / depth \uparrow

The more the positive on Gate terminal, So the channel width
and depth will increase.



$\uparrow V_{GS}$
 \downarrow

Width of
channel increase

$V_{GS} > \text{(particular voltage)}$
then channel width is
sufficient to allow
the flow of current
 I_D

$V_T \rightarrow$ The voltage which result, significant amount
of current to flow from source to drain is
known as threshold voltage.

Threshold voltage
 V_T

$V_{GS} > V_T, I_D \uparrow$

We did not want to many
biasing source

$$V_G - V_{GS} + V_{DS} = V_D$$

$$V_{GS} - V_D = V_{GS} - V_{DS}$$

$$V_{GD} = V_G - V_D = V_{GS} - V_{DS}$$

Case 1 = $V_{DS} = 0V$

$$V_{GD} = V_{GS}$$

Width of depletion region will be uniform

$$V_T = 1V$$

$$V_{GS} = 2V = V_{GD}$$

$$\text{Excess voltage} = V_{GS} - V_T = 1V$$

$$C_{H1} \rightarrow 1V$$

$$V_{GS} = 4V = V_{GD}$$

$$C_{H3} \rightarrow 3V$$

Case 2 = $V_{GS} = 3V = V_{GD}$

$$C_{H2} \rightarrow 3 - 1 = 2V$$

$$C_{H1} < C_{H2} < C_{H3}$$

Case 2: $V_{DS} > 0V$

$$V_{GD} = V_{GS} - V_{DS} \quad \downarrow$$

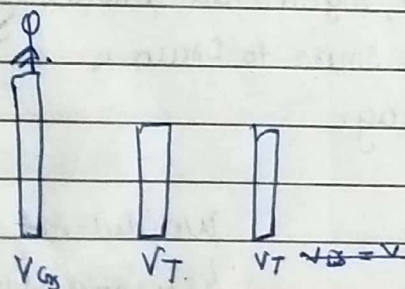
Drain is becoming more positive than the gate.

Depletion region is not uniform since $V_{GD} > V_{GS}$.

Width of channel will reduce and width of depletion region will increase.

Case 3: $V_{DS} = V_{GS} - V_T$

$$V_{GD} = V_T$$



So the channel will become very narrow and width will be almost zero, it will happen only here.

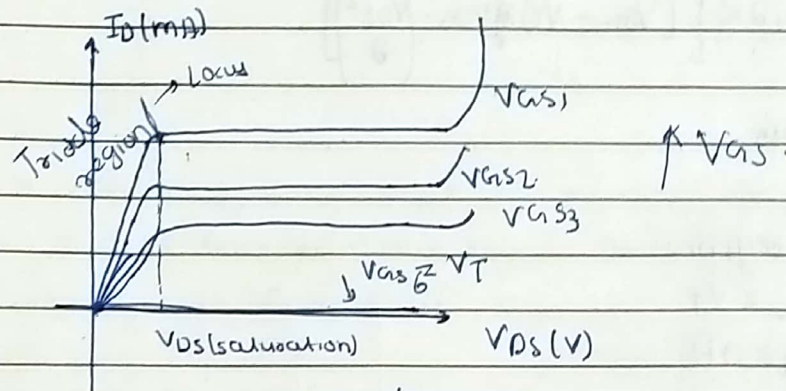
This condition is known as pinch off

Draw characteristics of Enhancement-Type MOSFET

Output characteristics

O/p i $\rightarrow I_D$ control variable $\rightarrow V_{GS}$
O/p V $\rightarrow V_{DS}$

Dr ch $\rightarrow I_D$ vs V_{DS} for various levels of V_{GS}



cutoff-off region

$$V_{DS}(\text{saturation}) = V_{GS} - V_T$$

V_T and k

Case I: $V_{GS} > V_T$

$$V_{eff} = V_{GS} - V_T$$

$$V_{DS} = 0 \Rightarrow V_D = V_S \quad V_{DS} \uparrow \rightarrow I_D \uparrow$$

$$V_{DS} = V_{DS}(\text{saturation}) \Rightarrow I_D = \text{constant (pin off)}$$

$$V_{DS} + V_{GD} - V_{GS} = 0$$

$$V_{GD} = V_{GS} - V_{DS}$$

$$V_{GD} = V_T$$

Case II $V_{GS2} > V_{GS1}$

$\uparrow V_{GS} \Rightarrow$ channel width \uparrow

$$I_2 < I_1$$

$$R_2 > R_1$$

slope 2 < slope 1

conductivity \uparrow
resistance \downarrow

Saturation - Regions

$$V_{DS} \geq V_{GS} - V_T$$

$$I_D = K(V_{GS} - V_T)^2$$

constant depends upon W/L

$$K = \frac{I_D}{(V_{GS} - V_T)^2} \quad A/V^2$$

Triode Region

$$V_{DS} < V_{GS} - V_T$$

$$I_D = 2K \left[(V_{GS} - V_T) V_{DS} - \frac{V_{DS}^2}{2} \right]$$

drain

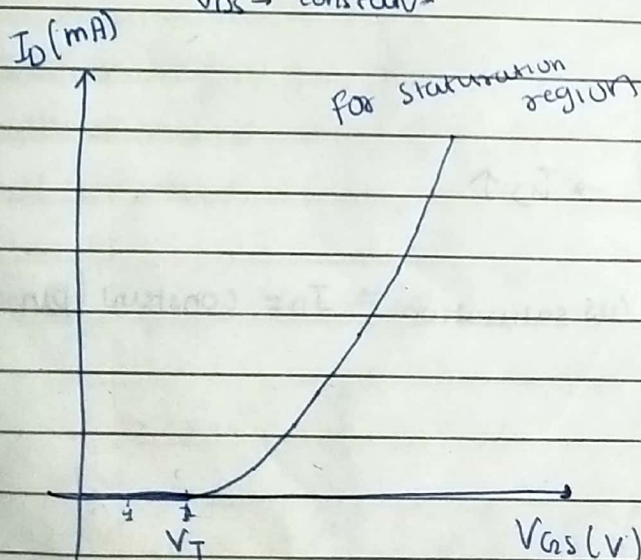
Cut off regions

$$V_{GS} < V_T$$

$$I_D = 0A$$

Transfer Characteristics of Enhancement Type MOSFET

$V_{DS} \rightarrow \text{constant}$

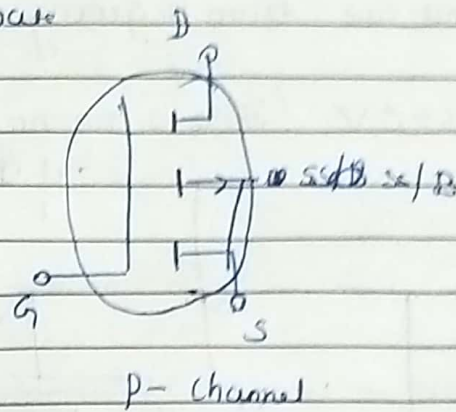
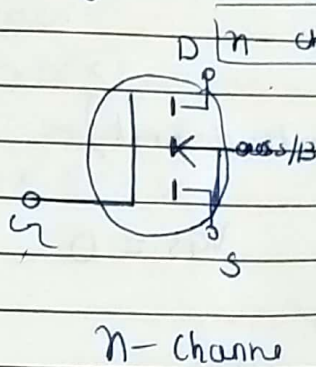


$$V_{DS} \geq V_{GS} - V_T$$

In saturation

$$I_D = K(V_{GS} - V_T)^2$$

$\text{SiO}_2 \rightarrow$ to insulate the gate from drain, source and substrate
So that gate current will become zero. Due to this input impedance will be higher. Hence the gain will be higher.

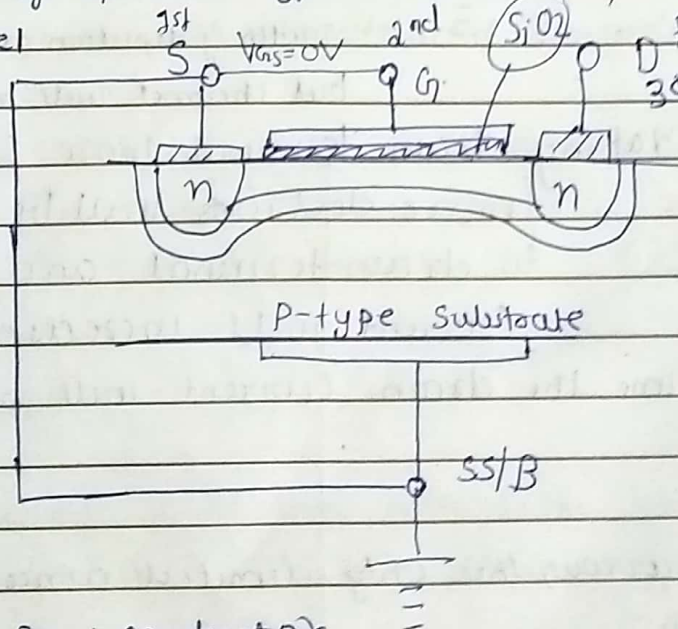


ii) Region for arrow

Arrow indicates the direction of drain current for n-channel, drain current goes into MOSFET through drain region and for p-channel drain current coming out of the drain region.

Construction of Depletion-Type MOSFET

n-channel



Input Impedance is high
channel is present
from beginning
to end.

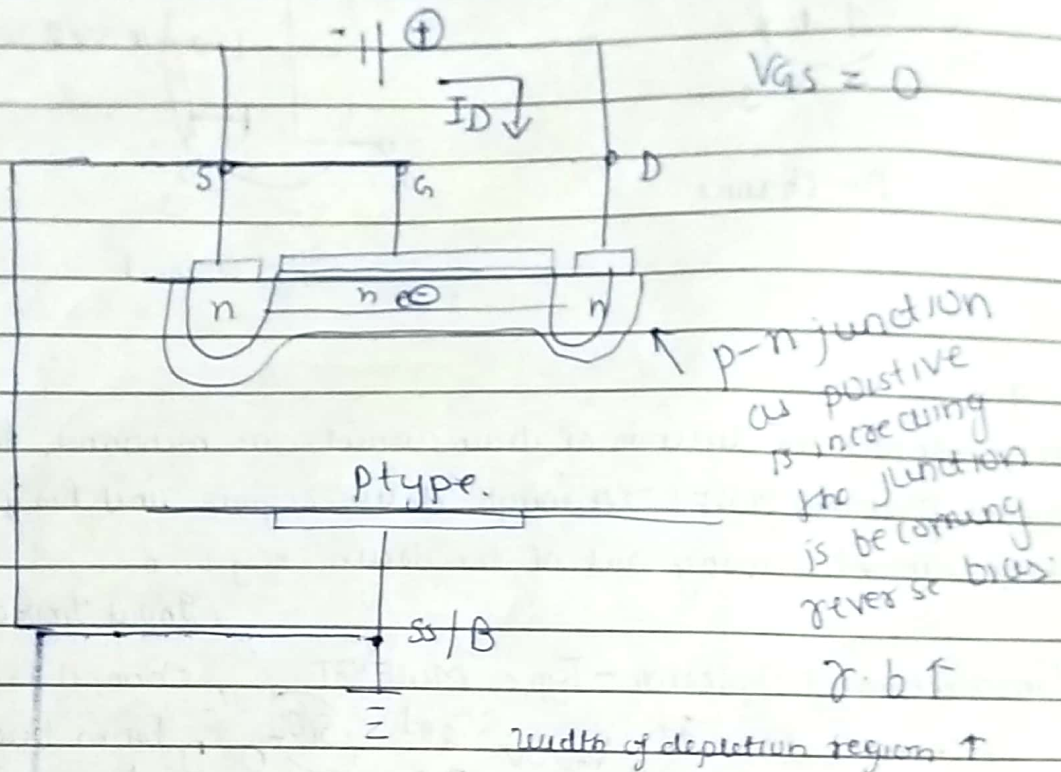
Metal oxide Semi-conductor

Working of Depletion-Type MOSFET

× N-channel JFET

Channel are form beginning

$V_{GS} = 0V$ (There is no need to enhance the channel)



width of depletion region ↑
but channel will become narrower

↑ V_{DS} | Making drain terminal more positive
| more electrons will be attracted to drain terminal and drain current will increase

But after some time the drain current will become constant.

The channel become narrow, then only limited amount of electrons will pass

$I_D \rightarrow \text{constant}$
 I_{DSS}

n-channel
JFET

D-MOSFET

I_{DSS} → Maximum

$V_{GS} = 0$

$V_{GS} > 0$ (X) cannot
be made

$V_{GS} \leq 0$

I_{DSS} → is not
maximum current

$V_{GS} = 0$

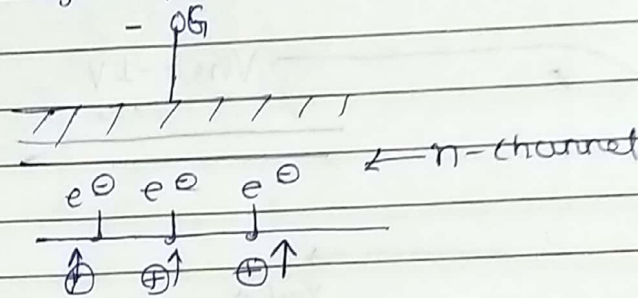
or $V_{GS} > 0$

$V_{GS} \rightarrow \begin{matrix} +ve \\ 0 \\ -ve \end{matrix}$

Case II

$V_{GS} = -1V \rightarrow$

negative potential at gate will repel the electrons



The electrons at n-channel will push the electrons in p-substrate and holes of p-channel are attracted towards n-channel.

Recombination takes place and available electrons for conduction will decrease. Due to less electrons present in n-channel the current I_D will also decrease.

Case III

$V_{GS} = +1V$

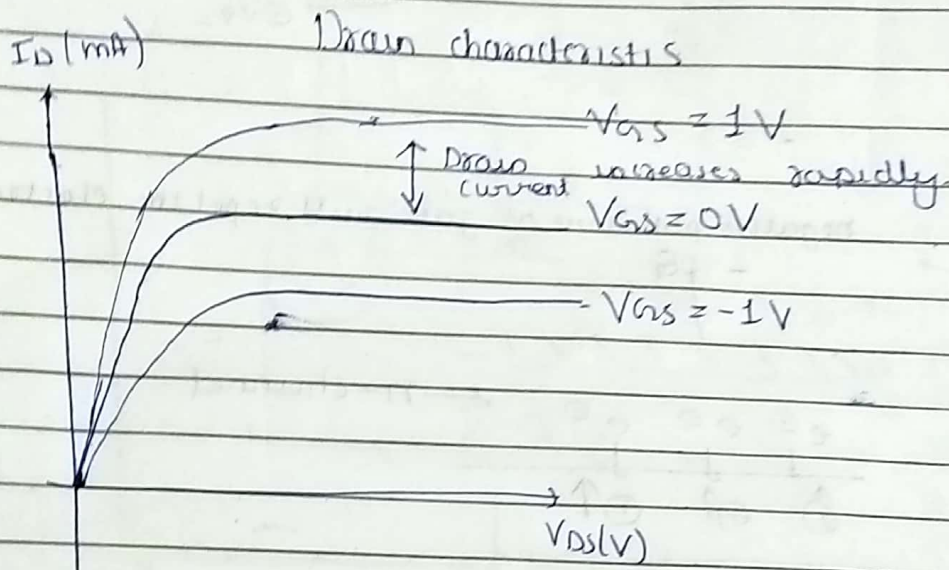
The positive potential at the gate; attract the minority charge carriers (e^-) from p-substrate; collision will occur between accelerating particles,

$I_D \uparrow$ rapidly

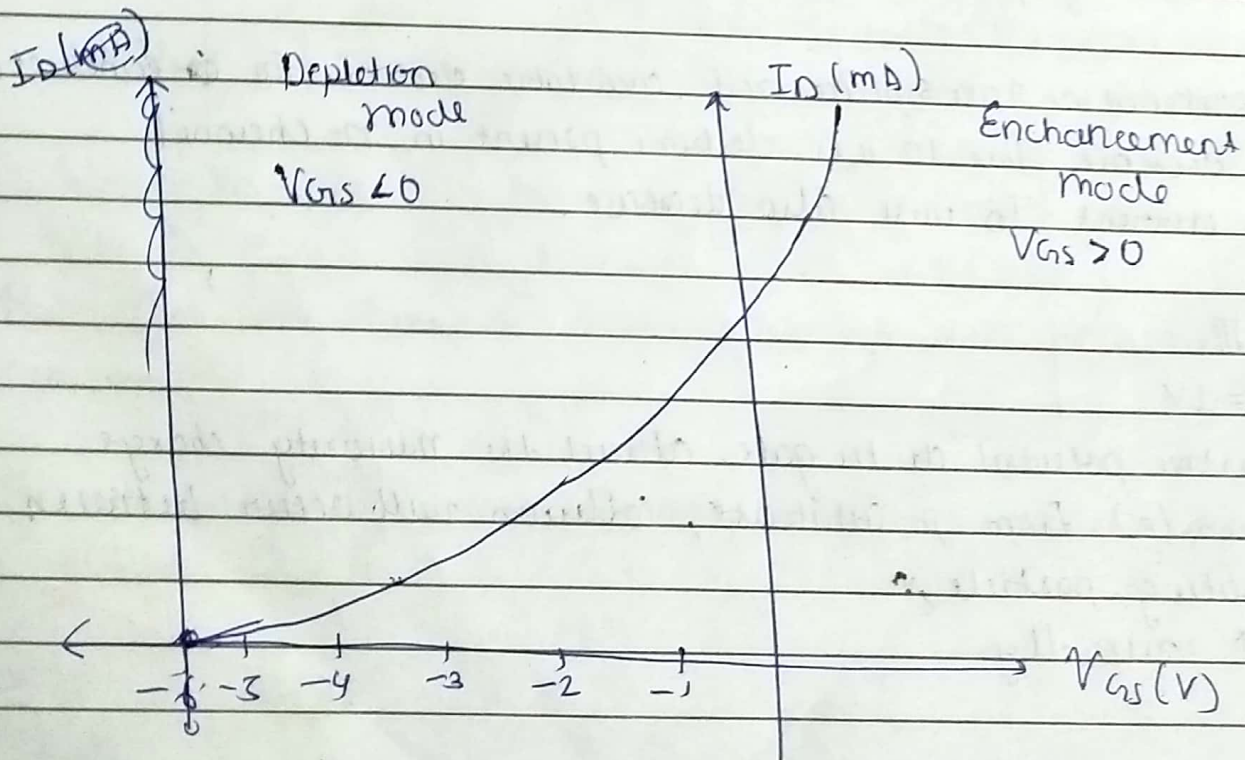
Drain and Transfer characteristics of Depletion-Type MOSFET

o/p I_D vs $V_{DS} \rightarrow$ o/p
for various $V_{GS} \rightarrow$ i/p voltage

o/p I_D vs $V_{GS} \rightarrow$ i/p
for fixed V_{DS}



① $V_{GS} = 0V \Rightarrow V_D - V_S = 0 \quad V_D = V_S$



We call it enhancement mode in D-MOSFET, bcoz as positive V_{gs} applied through gate, the width of n-channel between source and drain increases due to flow of electron from p-type substrate into n-type channel. Hence drain current also increased due to the width of n-channel. Thus the drain current enhances so we called it enhancement mode.

